

AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A chemical-amplification positive-working photoresist composition which comprises, as a uniform solution in an organic solvent:

(A) a polyhydroxystyrene-based resinous ingredient of which the hydroxyl groups are partly substituted by acid-dissociable substituent groups capable of being dissociated by interacting with an acid; and

(B) a radiation-sensitive acid-generating compound capable of releasing an acid by irradiation, said acid-generating agent being selected from the group consisting of diazomethane compounds and onium salt compounds of which the anionic counterpart is a C₁-C₁₅ halogenoalkylsulfonate anion,

the resinous ingredient as the component (A) being a combination comprising (A1) a first polyhydroxystyrene resin substituted for from 30 to 60% of the hydroxyl groups by tert-butoxycarbonyl groups and (A2) a second polyhydroxystyrene resin substituted for from 5 to 20% of the hydroxyl groups by tert-butoxycarbonyl groups which are the same as in the first polyhydroxystyrene resin (A1), wherein the ratio of the maximum weight-average molecular weight Mw_{max} to the minimum weight-average molecular weight Mw_{min} in the first and second polyhydroxystyrene resins (A1) and (A2) is smaller than 1.3, and the weight proportion of said first and second polyhydroxystyrene resins (A1) to (A2) is in the range of ~~1:9 to 9:1~~ 4:6 to 1:9, and

(C) an amine compound.

2-6. (Canceled)

7. (Previously presented) The chemical-amplification positive-working photoresist composition as claimed in claim 1 in which the polyhydroxystyrene-based resinous ingredient as the component (A) is a combination of (A1) a first polyhydroxystyrene resin substituted for from 35 to 60% of the hydroxyl groups by the acid-dissociable substituent groups and (A2) a second polyhydroxystyrene resin substituted for from 5 to 15% of the hydroxyl groups by the acid-dissociable substituent groups.